

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|--|--|------------------|---------|------------------|
| L1 | 10635 | ((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2004/12/03 19:49 |
| L2 | 3814 | ((photo near2 resist) near2 (layer or film)) same ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 19:14 |
| L3 | 31804 | ldd or (lightly near2 dop\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:43 |
| L4 | 56 | 2 same 3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:43 |
| L5 | 8 | 1 and 4 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:45 |
| L6 | 48 | 4 not 5 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:49 |
| L7 | 56 | ((photo near2 resist) near2 (layer or film)) same ((photo near2 mask\$1) or mask\$1) same (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:52 |
| L8 | 23 | ((photo near2 resist) near2 (layer or film)) same ((photo near2 mask\$1) or mask\$1) near10 (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:56 |
| L9 | 6 | (pattern\$3 near5 ((photo near2 resist) near2 (layer or film))) near10 (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:58 |

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| L10 | 2575 | (pattern\$3 near5 ((photo near2 resist) near2 (layer or film))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:58 |
| L11 | 31 | 10 same 3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:58 |
| L28 | 6545 | pattern\$3 near5 (photo near2 resist) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 19:59 |
| L29 | 77 | 28 same (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 19:16 |
| L30 | 11 | 29 and 1 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 19:17 |
| L31 | 66 | 29 not 30 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 19:17 |
| L32 | 10933 | ((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/180) or (438/181) or (438/197) or (438/301) or (438/364) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2004/12/03 19:54 |
| L33 | 181 | 32 and 28 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 20:00 |
| L34 | 58 | 33 and 3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 20:01 |

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| S1 | 10043 | ((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2004/12/03 18:30 |
| S2 | 30291 | ldd or (lightly near2 dop\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:42 |
| S3 | 3632 | (photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/03 18:31 |
| S4 | 16861 | ((poly near2 crystall\$3) or poly) near2 silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:09 |
| S5 | 458116 | tft or (thin near2 film) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:15 |
| S6 | 337 | (ldd or (lightly near2 dop\$3)) and ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 19:39 |
| S7 | 10 | (((ldd or (lightly near2 dop\$3)) and ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1))) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 19:55 |

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| S8 | 1 | ((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) and (((ldd or (lightly near2 dop\$3)) and ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1))) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 19:40 |
| S9 | 5 | ((ldd or (lightly near2 dop\$3)) and ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1))) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 19:55 |
| S10 | 38 | ((ldd or (lightly near2 dop\$3)) and ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1))) and (((poly near2 crystall\$3) or poly) near2 silicon)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:06 |
| S11 | 2 | (((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon)) and (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:07 |

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|-----|-------|--|---|----|----|------------------|
| S12 | 11 | ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon)) and (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:08 |
| S13 | 64 | ((photo near2 resist) near2 (layer or film) same ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:16 |
| S14 | 10301 | (source same drain) near10 (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:16 |
| S15 | 803 | ((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((poly near2 crystall\$3) or poly) near2 silicon)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:17 |
| S16 | 372 | (((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:17 |
| S17 | 56 | (((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:17 |
| S18 | 3093 | (photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:07 |
| S19 | 159 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:29 |

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|-----|-----|--|---|----|----|------------------|
| S20 | 13 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:26 |
| S21 | 0 | (((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.)) not (((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3)))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:29 |
| S22 | 146 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3))) not (((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) and ((source same drain) near10 (ldd or (lightly near2 dop\$3)))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:29 |

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|-----|-------|---|---|----|----|------------------|
| S23 | 31623 | ((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:14 |
| S24 | 104 | (((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) same ((source same drain) near10 (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:42 |
| S25 | 10 | (((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) same ((source same drain) near10 (ldd or (lightly near2 dop\$3))) and (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:44 |
| S26 | 136 | (((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:44 |
| S27 | 31 | (((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon)) and (ldd or (lightly near2 dop\$3)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:44 |
| S28 | 30 | ((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) near10 ((source and drain) and (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:51 |
| S29 | 117 | ((photo near2 resist) or resist) same ((photo near2 mask\$1) or mask\$1)) near10 ((source and drain) and (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:55 |
| S30 | 36 | (((photo near2 resist) or resist) same ((photo near2 mask\$1) or mask\$1)) near10 ((source and drain) and (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:52 |

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| S31 | 31 | ((((photo near2 resist) or resist) same ((photo near2 mask\$1) or mask\$1)) near10 ((source and drain) and (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.)) not (((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1)) near10 ((source and drain) and (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:52 |
| S32 | 307 | ((photo near2 resist) or resist) near10 (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:56 |
| S33 | 198 | ((photo near2 resist) or resist) near5 (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:58 |
| S34 | 9 | (((photo near2 resist) or resist) near5 (((poly near2 crystall\$3) or poly) near2 silicon)) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 20:56 |
| S35 | 229 | (photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near10 ((ion near2 implant\$4) or dop\$) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:22 |

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| S36 | 6 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near10 ((ion near2 implant\$4) or dop\$)) and (ldd or (lightly near2 dop\$3))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:09 |
| S37 | 73 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near10 ((ion near2 implant\$4) or dop\$)) and (ldd or (lightly near2 dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:10 |
| S38 | 56 | ((photo near2 resist) or resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near10 ((poly near2 crystall\$3) or poly) near2 silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:17 |
| S39 | 7 | (((photo near2 resist) or resist) near5 (layer or film) same ((photo near2 mask\$1) or mask\$1) near10 ((poly near2 crystall\$3) or poly) near2 silicon) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:18 |
| S40 | 94 | ((photo near2 resist) or resist) near5 (layer or film) same ((photo near2 mask\$1) or mask\$1) near10 ((poly near2 crystall\$3) or poly) near2 silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:19 |
| S41 | 157 | (photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near5 ((ion near2 implant\$4) or dop\$) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:31 |
| S42 | 10 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near5 ((ion near2 implant\$4) or dop\$)) and (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:25 |

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| S43 | 48 | ((photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near5 ((ion near2 implant\$4) or dop\$)) and (tft or (thin near2 film)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:25 |
| S44 | 1 | (photo near2 resist) near5 (pattern\$3) same ((photo near2 mask\$1) or mask\$1) near5 ((ion near2 implant\$4) or dop\$) same ((poly near2 crystall\$3) or poly) near2 silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/10 21:32 |
| S45 | 20174 | (((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:56 |
| S46 | 16861 | ((poly near2 crystall\$3) or poly) near2 silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:10 |
| S47 | 303223 | (ion near2 implant\$4) or dop\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:16 |
| S48 | 124 | (((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:14 |
| S49 | 84 | ((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) same (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:18 |
| S50 | 511 | ((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:14 |
| S51 | 391 | ((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:14 |

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| S52 | 458116 | tft or (thin near2 film) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:15 |
| S53 | 191 | ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:47 |
| S54 | 10043 | ((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2004/08/11 11:15 |
| S55 | 19 | ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:16 |

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| S56 | 172 | (((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) not ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:34 |
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| S57 | 0 | ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) not (((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.))) not (((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:34 |
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| S58 | 219 | <p> (((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) not ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film)) not ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film)) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.))) </p> | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:35 |
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| S59 | 200 | (((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) not (((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) not ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and ((ion near2 implant\$4) or dop\$3)) and (tft or (thin near2 film))) and (((438/149) or (438/151) or (438/163) or (438/164) or (438/166) or (438/197) or (438/301) or (438/365) or (438/369) or (438/486) or (438/488) or (438/491) or (438/514) or (435/552) or (438/708) or (438/725) or (438/736) or (438/737)).CCLS.))) not ((((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:47 |
| S60 | 215 | (((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near10 ((photo near2 mask\$1) or mask\$1)) and (((poly near2 crystall\$3) or poly) near2 silicon)) and (tft or (thin near2 film))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:49 |
| S61 | 16906 | (((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near5 ((photo near2 mask\$1) or mask\$1) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:57 |

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| S62 | 1373 | ((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near5 ((photo near2 mask\$1) or mask\$1)) same (tft or (thin near2 film)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:58 |
| S63 | 507 | ((((photo near2 resist) or ((photo or light) near2 sensitive) or resist) near2 (layer or film)) near5 ((photo near2 mask\$1) or mask\$1)) same (tft or (thin near2 film))) and ((ion near2 implant\$4) or dop\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 11:59 |
| S64 | 5 | ("5037766" "5372958" "5462887" "5504019" "5529937").PN. | USPAT | OR | OFF | 2004/08/11 12:29 |
| S65 | 2 | ("5985741" "6066547").PN. | USPAT | OR | OFF | 2004/08/11 12:39 |
| S66 | 18 | ("4549843" "4655874" "4676868" "4764483" "4824802" "4865952" "4902899" "4952274" "5077234" "5110410" "5139608" "5175122" "5286581" "5296092" "5310621" "5350486" "5362591" "5418093").PN. | USPAT | OR | OFF | 2004/08/11 12:42 |
| S67 | 5 | ("5412493" "5736751" "5962916" "6365936" "6384427").PN. | USPAT | OR | OFF | 2004/08/11 12:44 |
| S68 | 1 | "6624443".URPN. | USPAT | OR | OFF | 2004/08/11 12:45 |
| S69 | 3 | ("4231811" "5985766" "6043000").PN. | USPAT | OR | OFF | 2004/08/11 12:46 |
| S70 | 0 | "6410211".URPN. | USPAT | OR | OFF | 2004/08/11 12:46 |
| S71 | 9 | ("3920483" "3997367" "4035226" "4137458" "4140913" "4144101" "4149904" "4163155" "4182023").PN. | USPAT | OR | OFF | 2004/08/11 12:47 |
| S72 | 155 | ((ldd or (lightly near2 dop\$3)) same (source and drain)) near10 simultan\$6 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 14:27 |
| S73 | 65 | ((ldd or (lightly near2 dop\$3)) same (source and drain)) near5 simultan\$6 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 14:32 |
| S74 | 91 | ((ldd or (lightly near2 dop\$3)) same (source and drain)) near5 (simultan\$6 or "same" adj time) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 14:33 |

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| S75 | 26 | ((l ^d d or (lightly near2 dop\$3)) same (source and drain)) near5 (simultan\$6 or "same" adj time)) not ((l ^d d or (lightly near2 dop\$3)) same (source and drain)) near5 simultan\$6) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/08/11 14:33 |
| S76 | 2 | "6452241".URPN. | USPAT | OR | OFF | 2004/08/11 14:35 |
| S77 | 2 | ("5914498" "6259120").PN. | USPAT | OR | OFF | 2004/08/11 14:36 |